



PATENT
Attorney Docket No. TI-25250
Application No.: 09/199,829
Customer No.: 23494

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
SMITH et al.) Group Art Unit: 2823
Application No.: 09/199,829) Examiner: Julio J. MALDONADO
Filed: November 25, 1998)
For: HYDROGEN PLASMA)
PHOTORESIST STRIP AND)
POLYMERIC RESIDUE)
CLEANUP PROCESS FOR)
OXYGEN-SENSATIVE)
MATERIALS)

Assistant Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In reply to the Office Action dated May 4, 2004, the period for reply having been extended for three months by a request for extension and fee payment filed concurrently herewith, please amend the application as follows:

Remarks begin on page 2 of this paper.